## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Robert Chau et al.

Serial No.: 10/618,226

Filed:

July 11, 2003

For:

A METHOD FOR MAKING A SEMICONDUCTOR

DEVICE HAVING A

HIGH-K GATE DIELECTRIC

Which is a Continuation of Application:

Serial No.: 10/082,530

Filed: F

February 22, 2002

Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

Examiner: Not yet assigned

Art Unit: 1765

Attorney Docket No: P12759C

Art Unit: 2825

Examiner: C. Lee

## INFORMATION DISCLOSURE STATEMENT

Sir:

This Information Disclosure Statement is being submitted under 37 C.F.R. §1.97(b). Enclosed is a copy of Information Disclosure Citation Form PTO-1449 together with copies of the references cited on that form. It is respectfully requested that the cited references be considered and that the enclosed copy of Information Disclosure Citation Form PTO-1449 be initialed by the Examiner to indicate such consideration and a copy thereof returned to applicant(s).

Pursuant to 37 C.F.R. § 1.97, the submission of this Information

Disclosure Statement is not to be construed as a representation that a search

has been made and is not to be construed as an admission that the information cited in this statement is material to patentability.

Respectfully submitted,

Dated: October 30, 2003

Mark V. Seeley Reg. No. 32,299

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## FIRST CLASS CERTIFICATE OF MAILING

(37 C.F.R. § 1.8(a))

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class mail with sufficient postage in an envelop addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

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Form PTO-1449 (Modified) Atty D cke							P12759C	Serial No.:	10/618	,226		
List of Patents and Publications Statement								Applicant:	Robert	Chau et al.		
(Use several sheets if necessary)							<u> </u>	Applicant.	RODGIL	Oriau et ai.		
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